

In the Abstract:

Please replace the Abstract with the following amended Abstract:

A method for performing a mask design layout resolution enhancement includes determining a level of correction for ~~the design layout~~ a mask design layout for a predetermined parametric yield with a minimum total correction cost. The mask design layout is corrected at ~~the~~ a determined level of correction based on a correction algorithm if the correction is required. In this manner, only those printed features on the mask design layout that are critical for obtaining ~~the~~ a desired performance yield are corrected, thereby reducing ~~the~~ total cost of correction of the mask design layout.